

Notice of References Cited		Application/Control No.	Applicant(s)/Patent Under Reexamination SCHAADT ET AL.	
		Examiner Eric B. Chen	Art Unit 1765	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	C	US-6,436,229	08-2002	Tai et al.	257/E21.218
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NON-PATENT DOCUMENTS

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	W	Rossnagel et al., Handbook of Plasma Processing, 1990, Noyes Publications, pp. 200-01.
	X	Ashurst et al., Journal of Microelectromechanical Systems, March 2001, Vol. 10, No. 1, pp. 41-49.

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.